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Serial No.: 09/387,894

Applicant: Amitava Guha, et al.

Filing Date: September 1, 1999

Group: 1742

## U.S. PATENT DOCUMENTS

| Initial* |    | Document No. | Date | Name | Class | Subcl.   | Filing Date |
|----------|----|--------------|------|------|-------|----------|-------------|
|          | AA |              |      |      |       |          |             |
|          | AB |              |      |      |       |          |             |
|          | AC |              |      |      |       | 10       |             |
|          | AD |              |      |      |       |          |             |
|          | AE |              |      |      |       | C        | 3           |
|          | AF |              |      |      |       | <u> </u> |             |
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|          | AH |              |      |      |       | <u> </u> |             |
|          | AI |              |      |      |       |          |             |
|          | AJ |              |      |      | -     |          |             |

## FOREIGN PATENT DOCUMENTS

| AK |   |  |  |
|----|---|--|--|
| AL | · |  |  |
| AM |   |  |  |
| AN |   |  |  |
| AO |   |  |  |
| AP |   |  |  |
| AQ |   |  |  |

## OTHER PRIOR ART

| NC        | Boyer et al., Metals Ha                        | andbook, Desk Edition, 1985, p.18-32.   |
|-----------|--|---|
| NL        | Harkness et al., "Beryl pp. 403-427, Vol. 2, E | lium-Copper and Other Beryllium-Containing Alloys", ASM Metals Handbook, dition 10, 1990. |
| Examiner: | Vicole COM                                     | Date Considered: 5/10/01  |

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformation with MPEP 609; draw line through citation if in conformance and not considered. Include copy of this form with next communication to applicant.